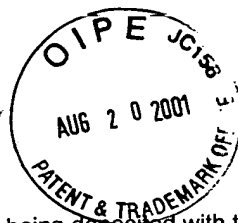


Docket No.: EHF 2001,0167 P



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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Norbert Benesch et al.  
Applic. No. : 09/873,230  
Filed : June 4, 2001  
Title : Method and Device for Optically Monitoring Fabrication Processes of Finely Structured Surfaces in a Semiconductor Production

INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks,  
Washington, D.C. 20231

Sir:

In accordance with 37 C.F.R. 1.98 copies of the following patents and/or publications are submitted herewith:

United States Patent No. 4,964,726 (Kleinknecht et al.), dated October 23, 1990;

United States Patent No. 5,703,692 (McNeil et al.), dated December 30, 1997;

United States Patent No. 5,830,611 (Bishop et al.), dated November 3, 1998;

German Published, Non-Prosecuted Patent Application DE 198 24 624 A1 (Bischoff), dated February 25, 1999, measuring arrangement for optical diffraction analysis of periodic sub micrometer structures;

European Patent Application EP 0 874 396 A2 (Waldhauer et al.), dated October 28, 1998;

Scott Bushman et al.: "Scatterometry Measurements for Process Monitoring of Polysilicon Gate Etch", SPIE, vol. 3213, 1997, pp. 79-90, XP-000890146;

Stephen A. Coulombe et al.: "Ellipsometric-Scatterometry for sub-0.1  $\mu\text{m}$  CD measurements", SPIE, vol. 3332, 1998, pp. 282-293, XP-000890148;

Jörg Bischoff et al.: "Optical scatterometry of quarter micron patterns using neural regression", SPIE, vol. 3332, 1998, pp. 526-537, XP-000890149;

N. Benesch et al.: Application and cost analysis of scatterometry for integrated metrology", SPIE, vol. 3743, May 1, 1999, pp. 25-32, XP-000890150;

Michael R. Murnane et al.: "Developed photoresist metrology using scatterometry", SPIE, vol. 2196, March 1994, pp. 47-59, XP-000890152;

Ilkka Kallioniemi et al.: "Optical scatterometry of subwavelength diffraction gratings: neural-network approach", Applied Optics, vol. 37, No. 25, September 1, 1998, pp. 5830-5835, XP-000890173.

If no translation of pertinent portions of any foreign language patents or publications mentioned above is included with the aforementioned copies of those applications, patents and/or publications, it is because no existing translation is readily available to the applicant.

Respectfully submitted,

  
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For Applicants

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Date: August 17, 2001

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